

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

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In re Patent Application of:  
Janusz Murakowski et al.

Confirmation No.: 1853

Application No.: 10/707,854

Filed: January 16, 2004

Art Unit: 2823

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For: ETCHLESS FABRICATION OF PLANAR  
PHOTONIC CRYSTAL STRUCTURES IN  
HIGH REFRACTIVE INDEX MATERIAL

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Examiner: F. L. Toledo

**AMENDMENT AFTER FINAL REJECTION**

**MS AF**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**August 15, 2006**

Dear Sir:

**INTRODUCTORY COMMENTS**

In response to the Final Office Action mailed August 8, 2006, the following Amendments and remarks are submitted to place the above-identified U.S. patent application in condition for allowance.

**Amendments to the Claims** begin on page 2 of this paper.

**Remarks/Arguments** begin on page 5 of this paper.

No fees are believed to be due with this Amendment after Final.